

2/11/04

Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No.	Application No.:
	NIKOP063/PA0 646	NEW
	Applicant:	
	Alton Hugh Phillips	
	Filing Date	Group
	HEREWITH	UNASSIGNED

U.S. Patent or Publication Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
HN	A1	6,570,645	5/27/03	Korenaga et al.			
	A2	6,037,680	3/14/00	Korenaga et al.			
	A3	5,841,250	11/24/98	Korenaga et al.			
	A4	6,177,987	1/23/01	Korenaga			
	A5	6,107,703	8/22/00	Korenaga			
	A6	6,678,038	1/13/04	Binnard			
	A7	6,618,120	9/9/03	Ueta			
	A8	6,597,435	7/22/03	Poon et al.			
	A9	6,555,936	4/29/03	Tanaka et al.			
	A10	6,538,719	4/25/03	Takahashi, et al.			
	A11	6,504,162	1/27/03	Binnard et al.			
	A12	6,496,248	12/17/03	Tanaka			
	A13	6,490,105	12/3/02	Hagy			
	A14	6,597,433	7/22/03	Renkens, et al.			
	A15	6,342,942	6/29/99	Uzawa			
	A16	2003/0223125	12/4/03	Sewell, Harry; et al.			
	A17	2002/0159046	10/31/02	Binnard et al.			
	A18	2002/0109823	8/15/02	Binnard et al.			
HN	A19	200/0041377	4/11/02	Hagiwara et al.			

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
HN	B1	EP1367444	3/12/03	EPO			X	
	B2	EP1376052	2/1/04	EPO			X	
	B3	EP1137054	9/26/01	EPO			X	
HN	B4	WO01/81171	11/1/01	WIPO			X	
HN	B5	JP2002313716 Accompanied by English- language abstract	10/25/02	JPO				X

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Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
HW	C1	Meiling et al., "Progress of the EUVL Alpha Tool," Proceedings of SPIE, Vol. 4343, pp. 38-50, 2001
	C2	Gui et al., "Extended Front-to-Back Alignment Capability for MEMS/MOEMS Applications," Proceedings of SPIE, Vol. 4688, pp. 867-873, 2002
	C3	Sluijk et al., "Performance Results of a New Generation of 300 mm Lithography Systems," Proceedings of SPIE, Vol. 4346, pp. 544-557, 2001
	C4	Klassen et al., "Dynamice Performance of DUV Step & Scan Systems and Process Latitude," Proceedings of SPIE, Vol. 4000, pp. 776-784, 2000
HW	C5	Meiling et al., "The EUV Program at ASML: An Update," Proceedings of SPIE, Vol. 5037, pp. 24-35, 2003
Examiner	H. Nguyen <div style="text-align: right;">Date Considered 6/23/05</div>	

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.